

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of: **Miwa KOZAWA et al.**

Art Unit: **1795**

Application Number: **10/720,097**

Examiner: **Daborah Chacko Davis**

Filed: **November 25, 2003**

Confirmation Number: **4454**

For: **PROCESS FOR FORMING RESIST PATTERN, SEMICONDUCTOR DEVICE  
AND FABRICATION THEREOF**

Attorney Docket Number: **032132**

Customer Number: **38834**

**AMENDMENT UNDER 37 C.F.R. § 1.111**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

May 17, 2010

Sir:

In response to the Office Action dated December 17, 2009, the response date of which having been extended by two months to May 17, 2010, Applicant amends the claims as follows and submits the following remarks.

Amendments to the Claims begin on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.